



SHEET 1 OF 2

INFORMATION DISCLOSURE  
CITATION IN AN  
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.  
**055071-0328**SERIAL NO.  
**10/756,829**

APPLICANT

**Robert John SOCHA, et al.**

FILING DATE

**January 14, 2004**

GROUP

**2825**

## U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code <sup>2</sup> (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
SM		US 6,413,684 B1	07/02/2002	Stanton	
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						Yes	No

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.

EXAMINER

/Suresh Memula/

DATE CONSIDERED

01/05/2007

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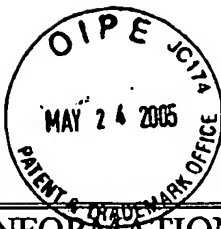


SHEET 2 OF 2

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EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.					
		Christoph DOLAINSKY, et al., "Simulation based method for sidelobe suppression," Optical Microlithography XIII, Proceedings of SPIE, 2000, pp 1156-1162, Vol. 4000					
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		<del>J. Pung CHEN, et al., "Practical Line OPC Contact Masks for Sub-0.5 Micron Design Rule Application: Part 4 - OPC Design Optimization," pp 181-201</del>					
		J.A. TORRES, et al., "Contrast-Based Assist Feature Optimization," Optical Microlithography XV, 2002, pp 179-187, Proceedings of SPIE, Vol 4691, SPIE					
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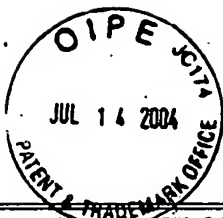
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						Yes	No
SM		WO 98/40791	09/17/1998	KONIN-KLIJKE PHILIPS ELECTRONICS N.V. [NL/NL]			
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